



**Editorial** 

## Acknowledgement to Reviewers of Journal of Manufacturing and Materials Processing in 2017

**IMMP** Editorial Office

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Received: 9 January 2018; Accepted: 9 January 2018; Published: 9 January 2018

Peer review is an essential part in the publication process, ensuring that *JMMP* maintains high quality standards for its published papers. In 2017, a total of 22 papers were published in the journal. Thanks to the cooperation of our reviewers, the median time to first decision was 14 days and the median time to publication was 37 days. The editors would like to express their sincere gratitude to the following reviewers for their time and dedication in 2017:

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